## Applicant(s)/Patent Under Application/Control No. Reexamination 10/617,487 SALAMA ET AL. Notice of References Cited Art Unit Examiner Page 1 of 1 2822 Monica Lewis U.S. PATENT DOCUMENTS Date **Document Number** Classification Name Country Code-Number-Kind Code MM-YYYY 257/500 US-2003/0222327 12-2003 Yamaguchi et al. Α 438/156 US-2003/0219933 11-2003 Yamauchi et al. В 257/492 11-2003 Parthasarathy et al. US-2003/0214009 C 257/491 10-2004 Onishi et al. US-200402112032 D 257/342 06-2004 Onishi et al. US-6,756,636 Ε 257/335 US-20040232483 11-2004 Kitagawa et al. 11-2004 438/268 Disney et al. US-6,815,293 G Kawaguchi et al. 257/341 US-6,297,534 10-2001 257/335 08-2004 Kitagawa et al. US-6,777,746 US-J US-Κ US-US-М FOREIGN PATENT DOCUMENTS

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(Use several sheets if necessary)				APPLICANT(1) SALAMA et al.					
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